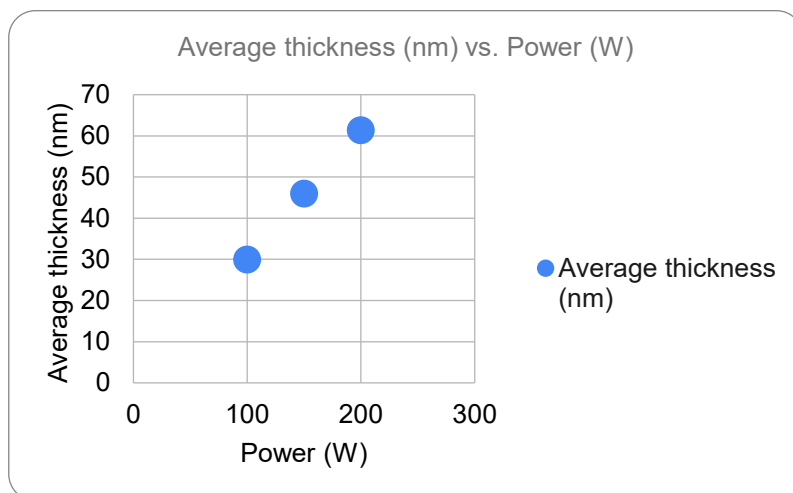


SiO2-RF

Power (W)	Thickness (nm)				Average thickness (nm)	Non uniformity (%)	Deposition rate (nm/min)	Time - 30mins
100	31.97	30.48	27.25		29.9	7.893	0.997	
150	45.86	45.87	46.06		45.93	0.218	1.531	
200	61.56	61.06	61.27		61.30	0.408	2.043	



Au-DC & RF

DC

Power (W)	Thickness (nm)					Average thickness (nm)	Non uniformity (%)	Deposition rate (nm/min)	Time - 15mins
50	137.7	135.5	142.1	142.22	152.8	142.048	6.09	9.470	
100	329	320	312.3	306.2	314	316.288	3.60	21.086	

RF

Power (W)	Thickness (nm)					Average thickness (nm)	Non uniformity (%)	Deposition rate (nm/min)	Time - 15mins
200	382.1	387	382.5	382.01	390.82	384.884	1.14	25.659	

Ti-DC & RF

DC

Power (W)	Thickness (nm)					Average thickness (nm)	Non uniformity (%)	Deposition rate (nm/min)	Time - 30mins
100	58.87	65.98	61.18			62.01	5.73	2.067	
150	97.6	103.9	103.7	99.43	97.45	100.414	3.21	3.347	

RF

Power (W)	Thickness (nm)					Average thickness (nm)	Non uniformity (%)	Deposition rate (nm/min)	Time - 30mins
200	80.61	75.56	82.07	78.67	83.93	80.168	5.22	2.672	

Pt-DC & RF

DC

Power (W)	Thickness (nm)					Average thickness (nm)	Non uniformity (%)	Deposition rate (nm/min)	Time - 15mins
100	142.1	142.6	141	142.94	164.67	146.632	8.09	9.775	
50	63.29					63.29	0.00	4.219	

RF

Power (W)	Thickness (nm)					Average thickness (nm)	Non uniformity (%)	Deposition rate (nm/min)	Time - 15mins
200	170.6	175.8	175.7	175.69	176.21	174.798	1.60	11.653	

Cr-DC & RF

Power (W)	Thickness (nm)					Average thickness (nm)	Non uniformity (%)	Deposition rate (nm/min)	Time - 30mins
100	128.1	135.9	136	130.67	131.9	132.502	2.99	4.417	
150	210.9	202.5	210.4	210.69	211.35	209.162	2.11	6.972	